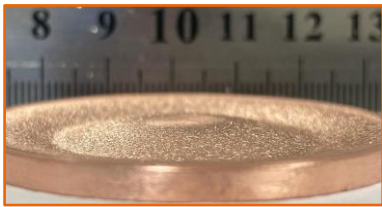


Stellar Sputter Sources



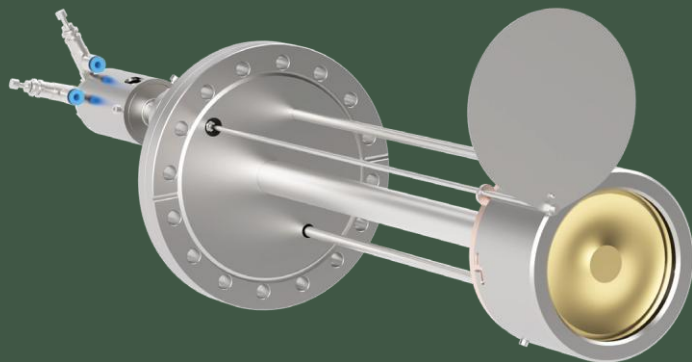
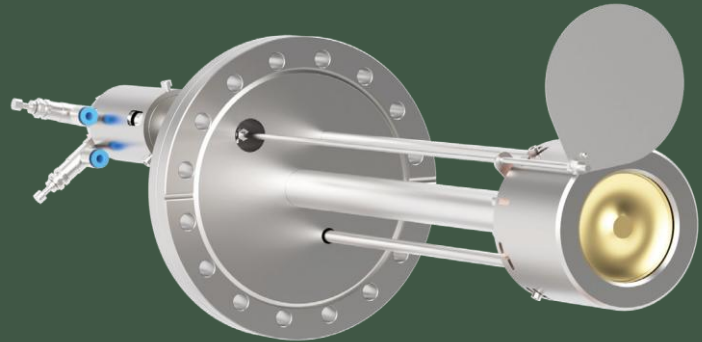
Bakeable to 150°C

Simple bayonet clamp

Excellent target
utilization up to 40%

Sputtering of
magnetic materials

Balanced or
unbalanced magnets



Fully UHV compatible
circular magnetrons



Stellar Sputter Sources

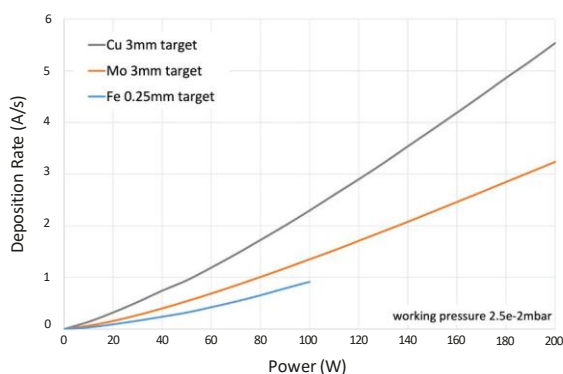
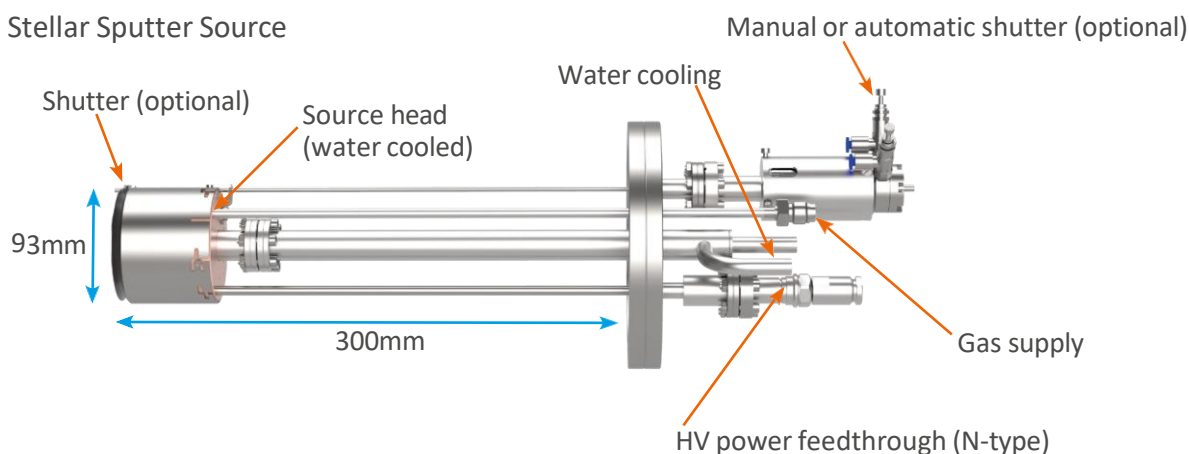


Fig.1. DC sputter rate for 2 inch target at 132mm working distance.

Nikalyte sputter sources can be supplied individually or added to a custom-built NEXUS or NL-FLEX vacuum system

Specifications

Schematic: 3" Stellar Sputter Source



Source Target Size	1.0" (25mm)	2.0" (50mm)	3.0" (75mm)
Mounting Flange (CF (O.D.))	4.5" 114mm NW63CF	6.0" 152mm NW100CF	6.0" 152mm NW100CF
UHV compatible	Bakeable to 150°C standard; 250°C bakeable option available (no need to remove magnets)		
In-vacuum length	200mm or 300mm - special length on request		
In-vacuum diameter of source head	45mm	72mm	93mm
Target thickness (non-magnetic targets with standard magnets)	Up to 3mm	Up to 3mm	Up to 3mm
Target thickness (non-magnetic targets with strong magnets)	n.a.	Up to 7mm	Up to 7mm
Target thickness (magnetic targets with strong magnets)	Not available - 0.4mm with standard magnets	Up to 1mm	Up to 2mm
Magnets	For magnetic or non-magnetic materials, balanced or unbalanced, easily exchanged by the user		
Power supply	DC, RF, Pulsed DC (unipolar or bipolar), HiPIMS		
Shutter	Integral manual or optional pneumatically operated		
Cooling	Minimum water flow of 1 l/min		

For further information please contact: sales@nikalyte.com

www.nikalyte.com



77 Heyford Park, Heyford Park Innovation Centre, Upper Heyford, Bicester, OX25 5HD, UK.

Follow us 

